

ABSTRACT

In the etching method of the present invention, a laminate film comprising at least one aluminum-based metal film and at least one molybdenum-based high-melting metal film is etched with a wet-etching solution comprising an aqueous solution containing phosphoric acid, nitric acid, an organic acid and a cation-generating component. By maintaining the water content of the wet-etching solution within the range of 10 to 30% by weight, the laminate film is wet-etched to have good normal tapers.



162162



G00002